L Number	Hits	Search Text	DB	Time stamp
2	1	("6627466").PN.	USPAT	2004/01/19 11:06
3	195	(wafer with fabrication) and apparatus and (wafer with handling) and	USPAT;	2004/01/19 11:06
		sensor and contaminant	US-PGPUB;	
Ī			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
4	36	(wafer with fabrication) and apparatus and (wafer with handling) and	USPAT;	2004/01/19 11:09
		sensor and contaminant and backside	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
5	3	(wafer with fabrication) and apparatus and (wafer with handling) and	USPAT;	2004/01/19 11:09
		(sensor with contaminant) and backside	US-PGPUB;	
		,	EPO; JPO;	
İ			DERWENT;	
			IBM_TDB	
-	6	(wafer adj handle\$) and contaminant and backside and capacitance	USPAT	2004/01/19 11:02
-	1	(wafer) and (detect with contaminant) and backside	USPAT	2003/04/16 13:46
	1	"5780204".PN.	USPAT	2003/04/16 13:45
-	1	"5710624".PN.	USPAT	2003/04/16 13:45
-	383	wafer adj handler	USPAT	2003/04/16 13:46
-	6	((wafer adj handler) and contaminant) and backside	USPAT	2003/04/16 13:46
-	33	(wafer adj handler) and contaminant	USPAT	2003/04/16 13:48
-	3	(wafer adj handler) and contaminant and capacitance	USPAT	2003/04/16 13:50
-	806	(438/14).CCLS.	USPAT	2003/04/16 13:50
_	24	((438/14).CCLS.) and (handler or carrier) and backside	USPAT	2003/04/16 13:51
-	5	((438/14).CCLS.) and (handler or carrier) and backside and (contaminant	USPAT	2003/04/16 13:53
		or defect)	1	
_	i	((438/14).CCLS.) and backside and (change with capacitance)	USPAT	2003/04/16 14:03
-	. 0	(detect adj defect) and (wafer with backside) and contaminant and	USPAT	2003/04/16 14:04
		(dielectric adj film)		
_	0	(detect adj defect) and (wafer with backside) and contaminant	USPAT	2003/04/16 14:04
_	0	(detect adj defect) and (wafer with backside) and capacitance	USPAT	2003/04/16 14:04
_	2	wafer and (liquid adj crystal) and (pressure with sensing) and detect and	USPAT	2003/04/16 14:09
		backside		
_	1	wafer and (defect or contaminant) and (sense with pressure with film)	USPAT	2003/04/16 14:55